



Meeting Agenda of the Japan Test Method Task Force Meeting
9th March, 2016 13:30-17:00 (Japan Standard Time)
Conference Room2 SEMI Japan Ichigaya, Tokyo, Japan

1. Introduction
Done
2. Agenda Review
Done
3. Required Meeting Elements
Done
4. Review of Previous Meeting Minutes & Previous Action Items
Done
5. Task Force Ballot Review
None
6. New Business
None
7. Old Business
 - 1) Confirmation of JEITA-SEMI transformation work schedule
 - 2) Regarding the Revision of MF1391-1107, Doc.5737A, Test method for substitutional atomic carbon content of silicon by infrared absorption.
 - 3) Progress of line item revision to SEMI Standard M85-00-1014: Guide for the Measurement of Trace Metal Contamination on Silicon Wafer Surface by Inductively Coupled Plasma Mass Spectrometry
 - 4) Regarding the NEW STANDARD: Doc 5770, Test Methods for Bulk micro defect density and denuded zone width in annealed silicon wafers.
 - 5) Other progress of the draft.
 - 6) Any other (if necessary)
Shiramizu さんご挨拶。。
8. Review of Action Items (if any)
 - 1)5737A submit
 - 2)窒素濃度(FT-IR)ドキュメントの JapanTF 内回覧
 - 3)SPVpre 処理の Int'ITF 回覧
 - 4)BMD/DZ、6月提出を目指す。
 - 5)Frank さんへ、コメントする。
9. Other Topics (if any)
10. Next Meeting Schedule
Will be discussed 6 月前半。(臨時 TF が 7 月前半かも)
11. Adjourn
This meeting might be closed at 17:00.